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(54) Title: PROCESS FOR THE PRODUCTION OF FLUOROETHANE AND USE OF THE PRODUCED FLUOROETHANE

(57) Abstract: A high-purity pentafluoroethane is produced through a process comprising (1) a step of fluorinating tetrachloroethylene to obtain a crude pentafluoroethane containing impurities and (2) a step of bringing the crude pentafluoroethane containing impurities into contact with oxygen and/or an oxygen-containing compound in the presence of a catalyst.



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